



INFORMATION DISCLOSURE CITATION

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Applicant	Nakamura et al.		
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U.S. PATENT DOCUMENTS

Examiner Initial*	Document Number	Issue Date	Name	Class	Sub Class	Filing Date if Appropriate
	5,889,686	3/30/99	Mimotogi et al.			

FOREIGN PATENT DOCUMENTS

Document Number	Publication Date	Country	Class	Sub Class	Translation Yes or No
2000-29217	1/28/00	Japan			Abstract
4-44312	2/14/92	Japan			Abstract
1-188859	7/28/89	Japan			Abstract

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

	Nakamura et al., "Influence of Alkaline Concentration Variation on CD in KrF Resist Development," Journal of Photopolymer Science and Technology (4/20/01), pp. 435-438
	Nakamura et al., "Impact of Development Reaction Products on CD in View of Developer Alkaline Concentration Deviation," SPIE (2001), p. 729

Examiner	Date Considered
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